The eBeam Initiative is a forum dedicated to the education and promotion of new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please e-mail requests@ebeam.org or visit www.ebeam.org

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Aki Fujimura, CEO of D2S, discusses the need for greater investments in simulation-based eBeam technology to support the continuation of Moore’s Law.

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Ryan Pearman of D2S explains why shapes taped out are not the shapes on the mask in the first part of a series on Photomask Processing and Modeling.

TECH TALK
Samsung and D2S evaluate a new measure of mask quality (eMEEF) for sub-100-nm and curved mask shapes.

PERSPECTIVES
Hugh Durdan of Xilinx offers a fabless manufacturer’s perspective on the implications of rising mask complexity and costs.

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